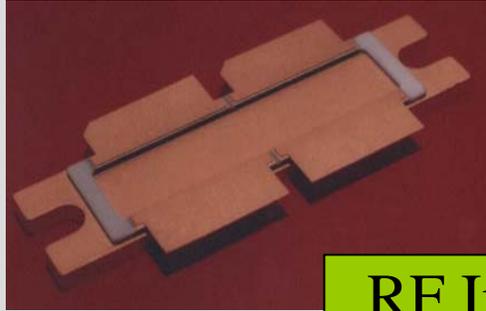
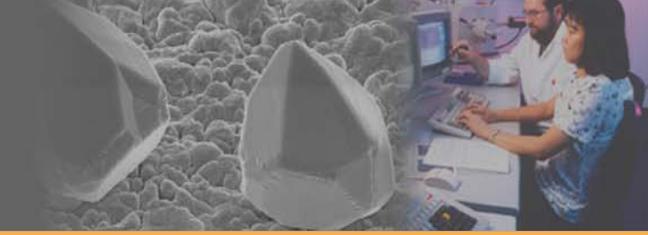


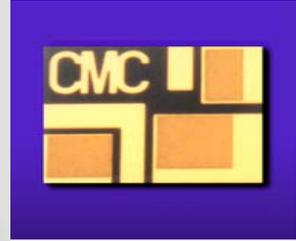


Material and Interfacial Impact on Package Thermal Performance

J.H. Harris, R. Enck, N. Leonardi, E. Rubel
CMC Interconnect Technologies



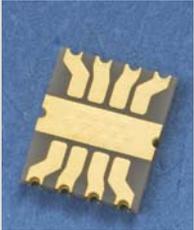
RF Infrastructure



Optics

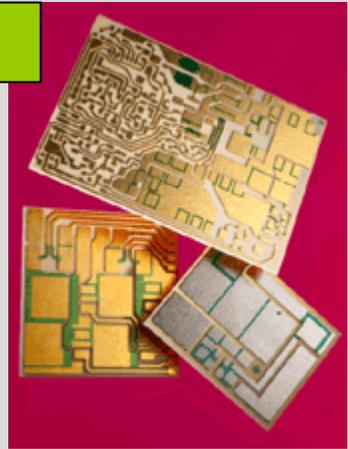
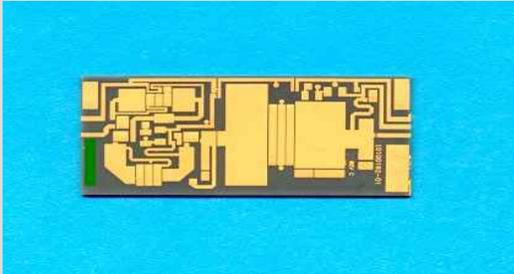


High Power Applications



Microwave

Power





Both materials and fabrication processes strongly impact thermal performance..

MATERIALS

PROCESSES

- High TC Components
- AlN Ceramics
 - Die Attach Materials
 - Diamond/Ag Composites

- Analysis
- Materials Science

- Consequences of Package Fab
- Material Changes
 - Formation of interfaces

PACKAGE THERMAL PERFORMANCE



Novel High Thermal Performance Materials for Packaging Applications

- Thermal Characterization- Laser Flash Technique
- Key Thermal Considerations for Packaging Applications- Processes
 - Material Changes during Package Fabrication
 - Thermal Impedance of Interfaces
 - Die Attach
- Conclusions

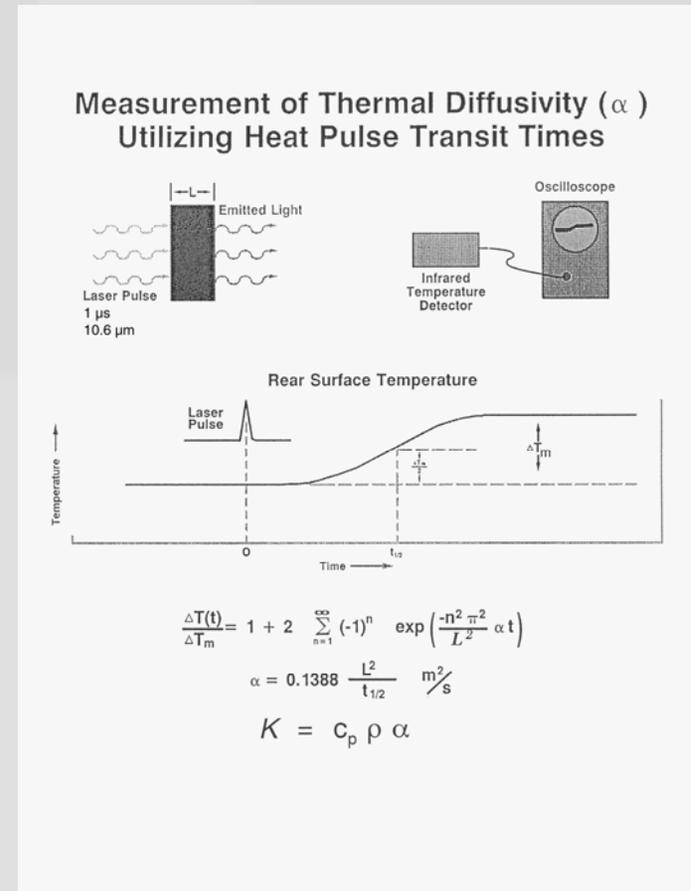


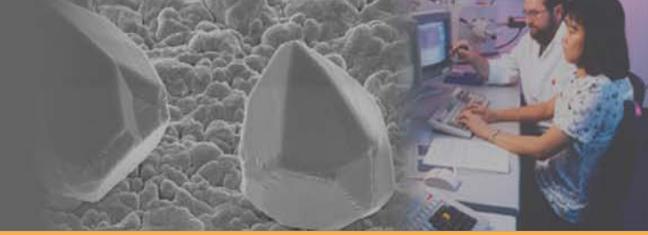
Laser Flash Thermal Diffusivity Measurement



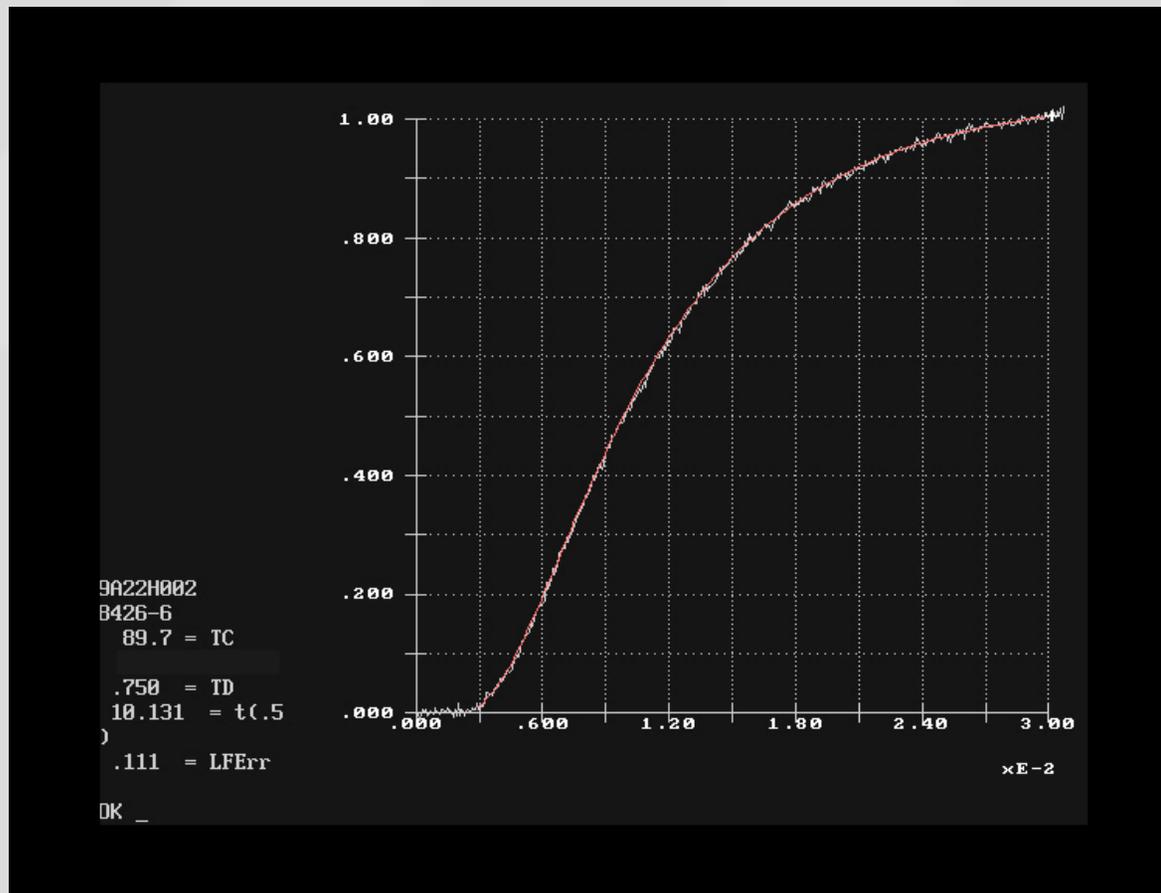
Laser Flash Thermal Diffusivity Measurement-Schematic

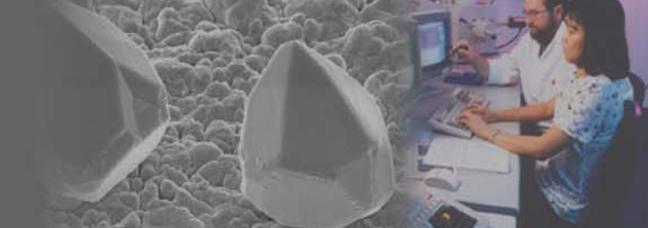
- Short laser pulse heats a shallow layer of the sample surface
- Temperature on the backside of the sample is monitored vs. time
- T vs. time curve is fit to 1D Heat Flow equation- Thermal Diffusivity is measured



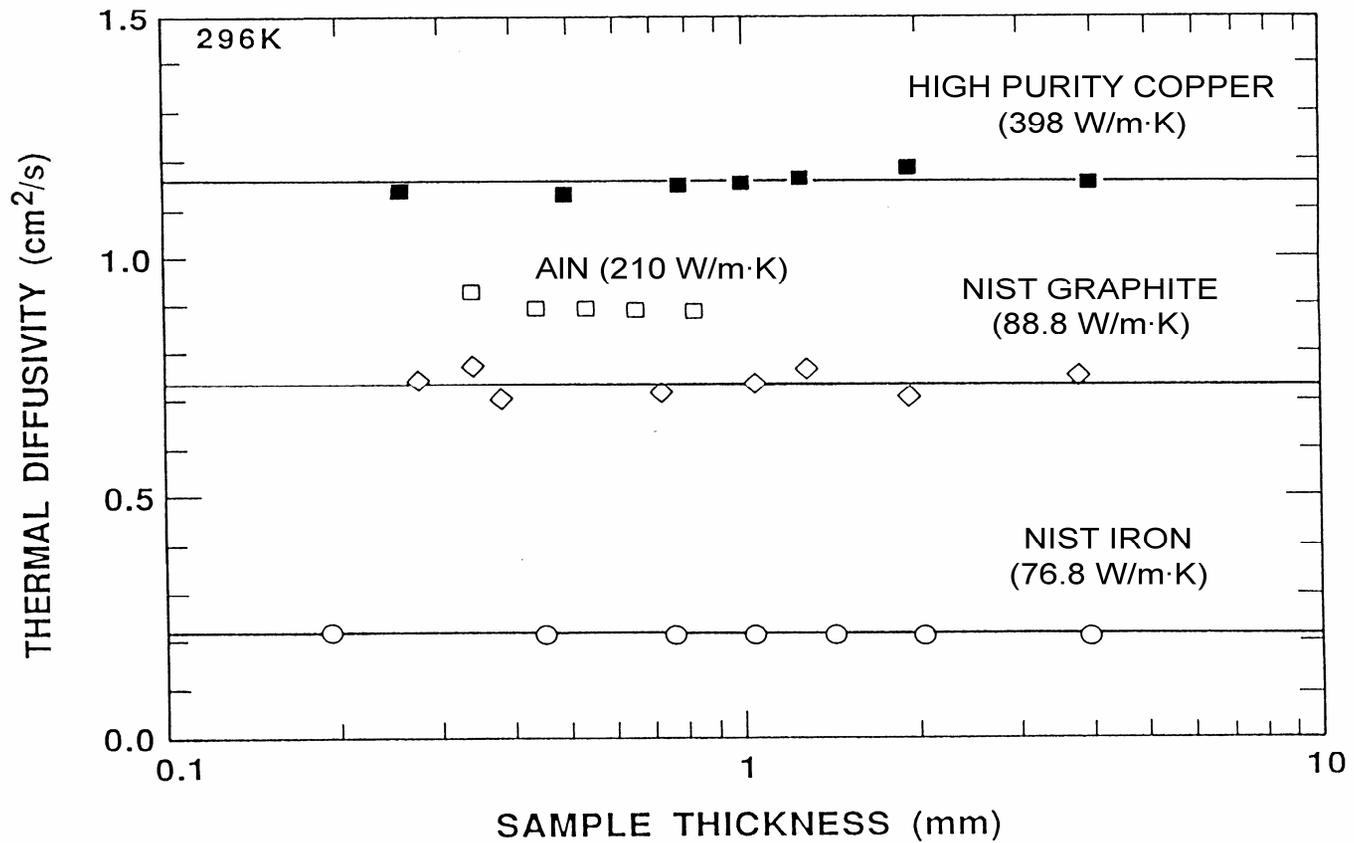


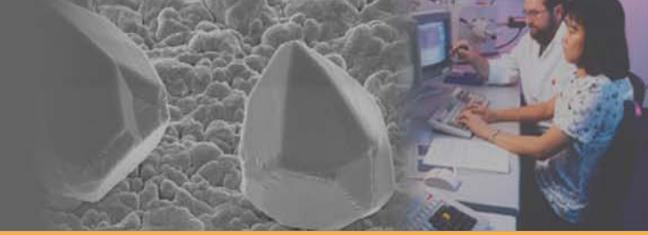
Laser Flash Thermal Diffusivity Measurement- T vs. Time



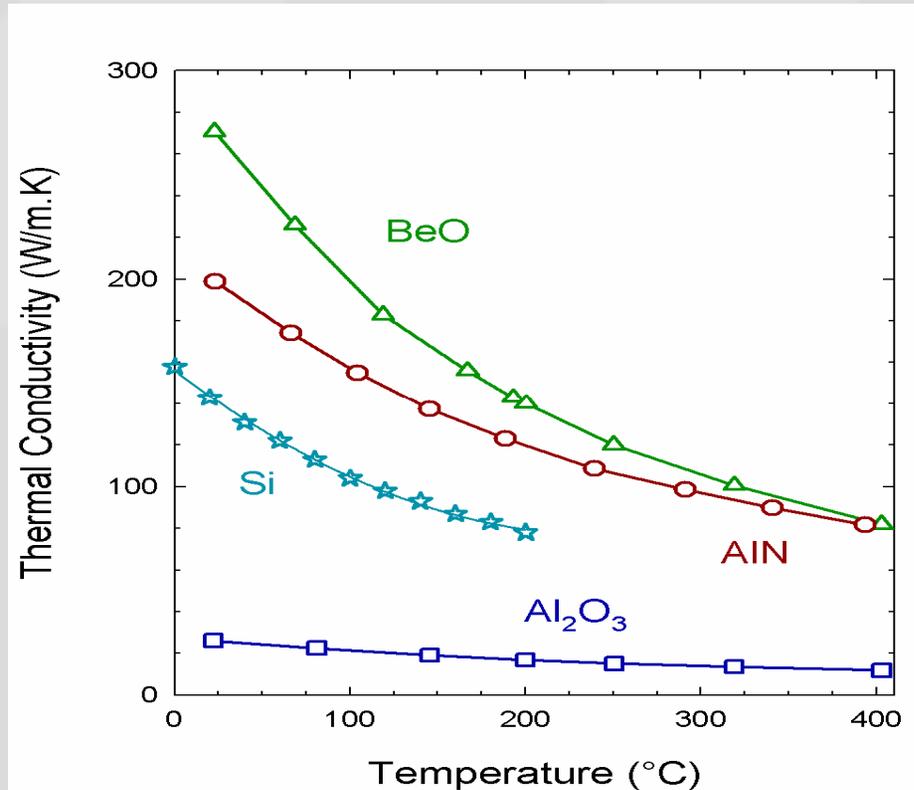


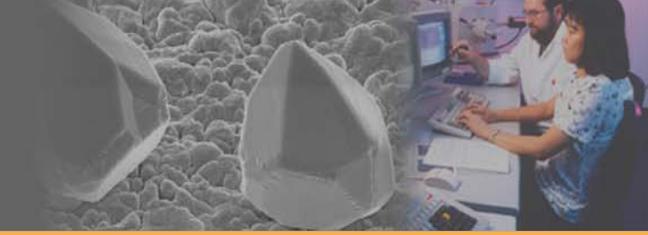
TC vs. Thickness





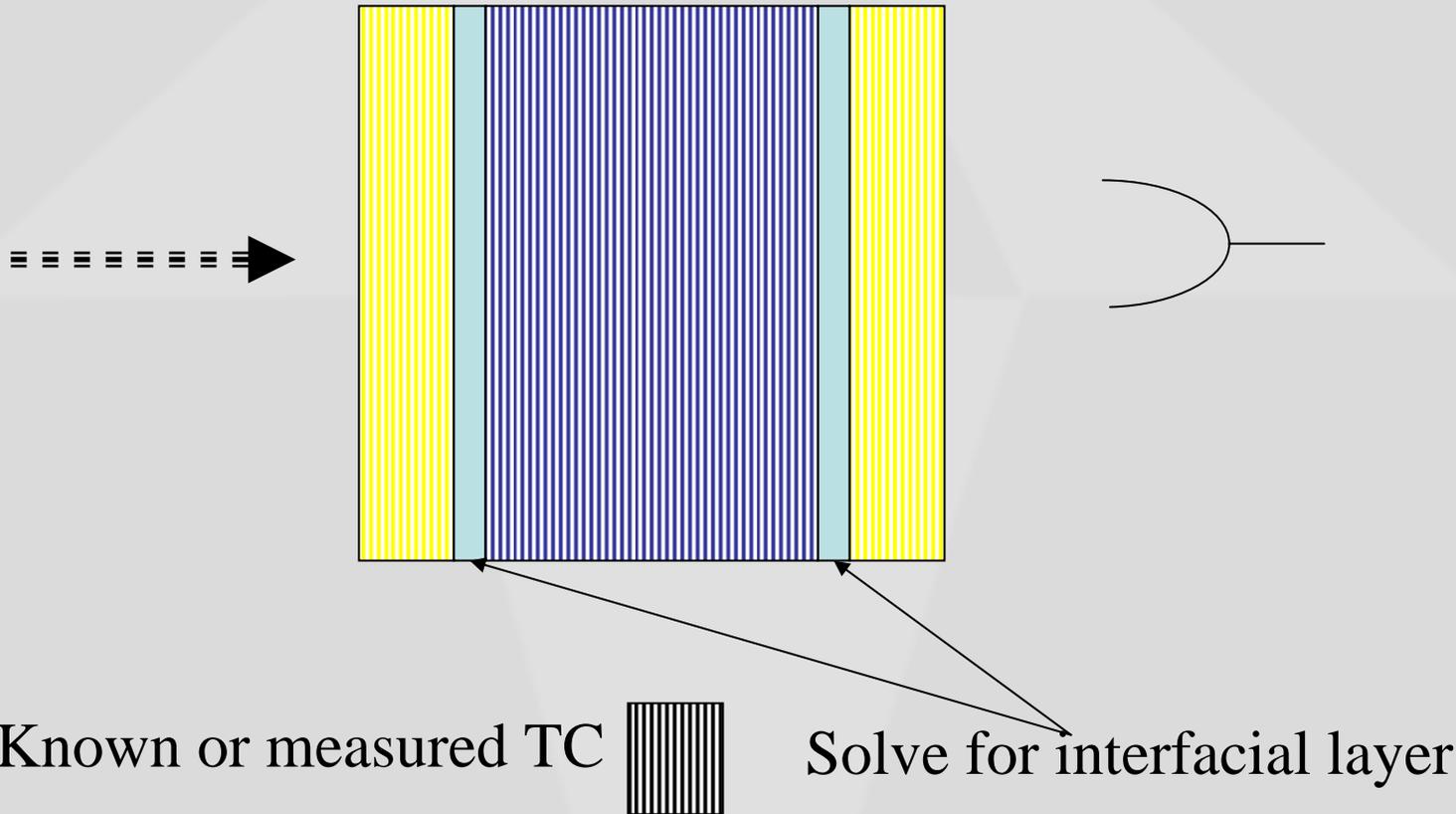
TC vs. Temperature





Thermal Characterization of Interfaces

Five Layer "Sandwich" Model*





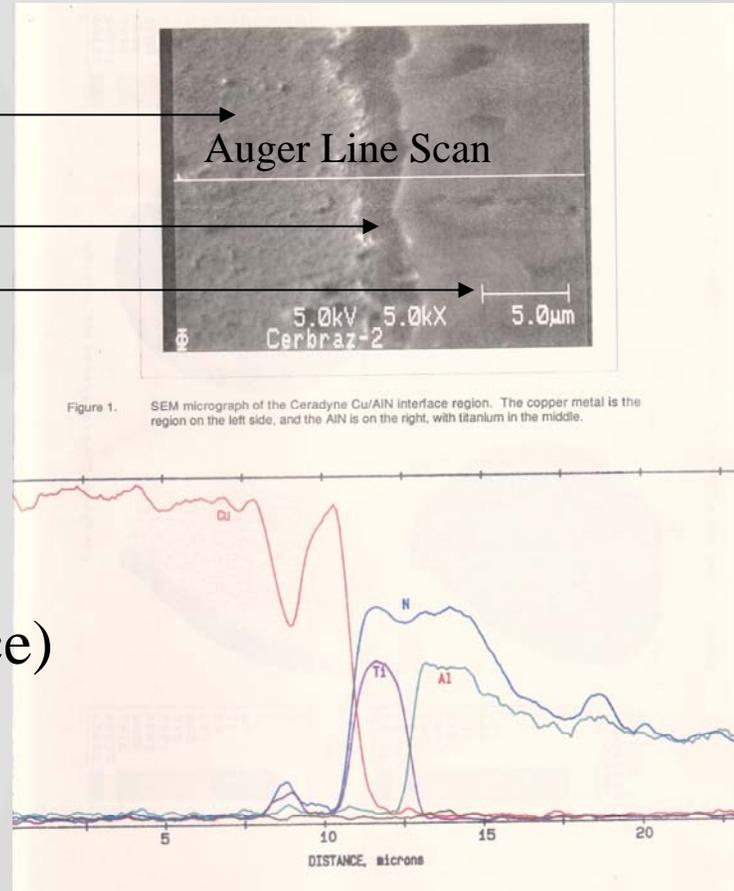
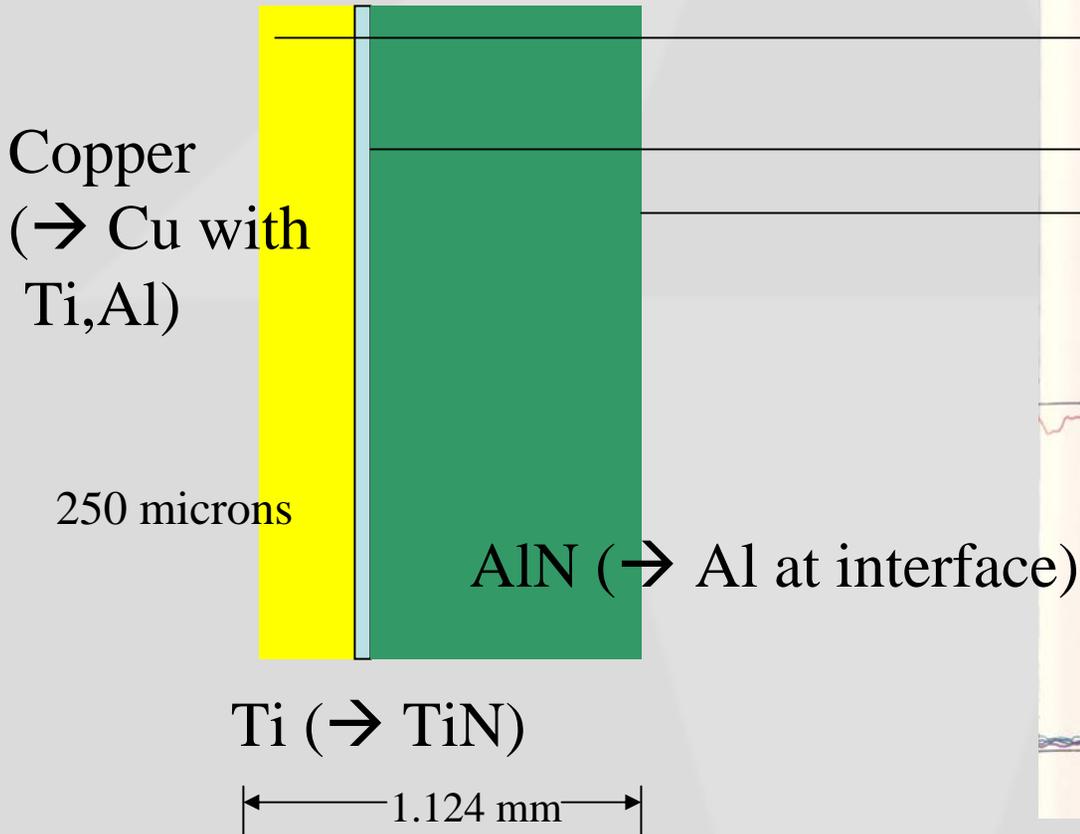
Material Changes During Fabrication

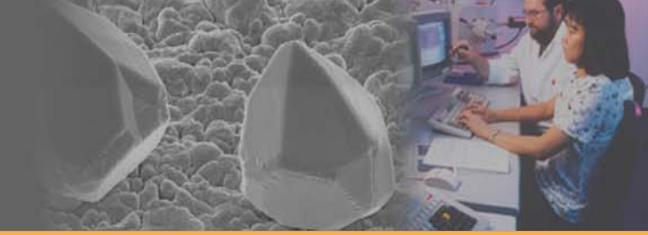
Copper Reactively Bonded to Aluminum
Nitride Ceramic



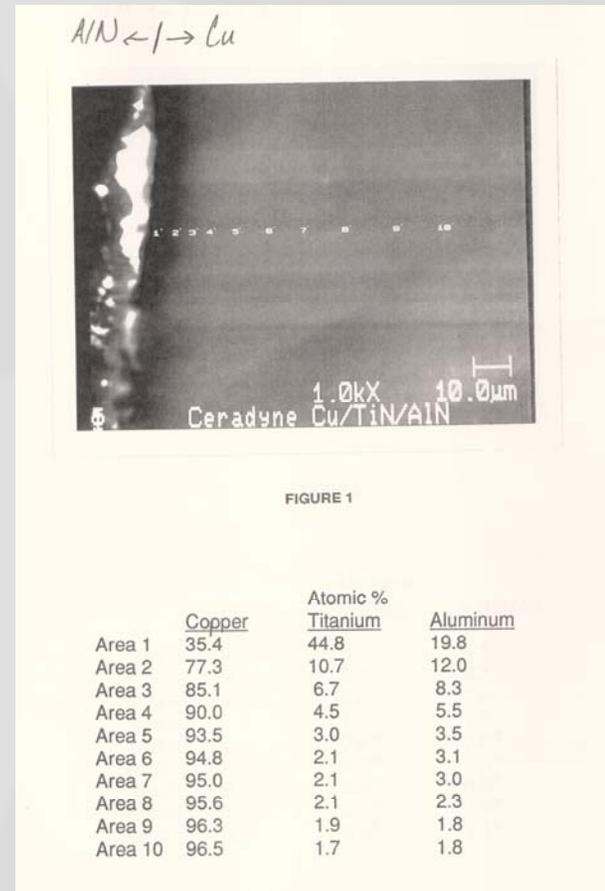
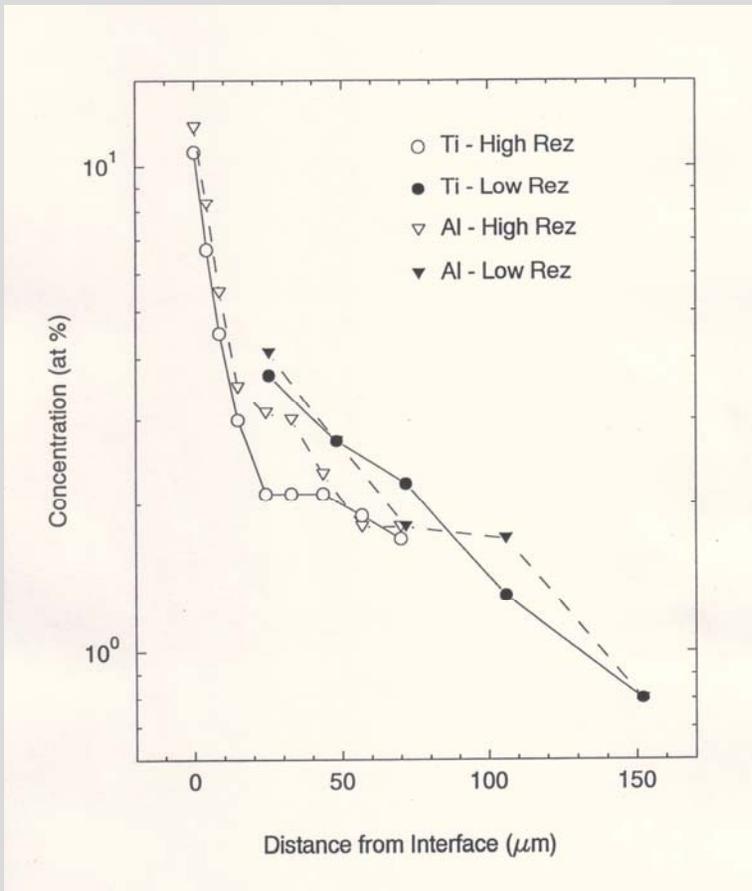
Copper Reactively Bonded to AlN

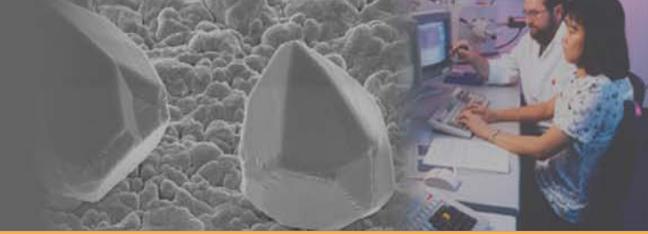
(→ Processed at 1000 ° C)





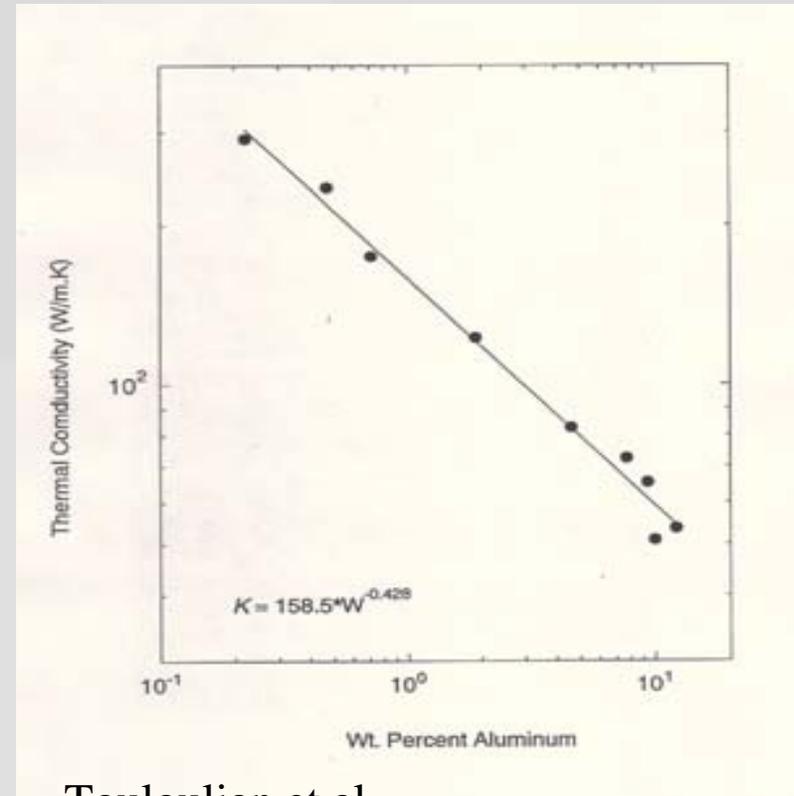
Auger Analysis of Ti, Al Diffusion into Copper





Copper TC vs. Dissolved Al

- TC can degrade rapidly with dissolved impurities (Ti, Al in Copper)
- Electron/ Impurity Potential scattering mechanism



Touloulian et al.



Thermal Properties of Cu Reactively Bonded to AlN

Percent of Total Thermal Resistance Contributed by Each Type of Layer

Sample	Two Metal Layers	Two Interface Layers	AlN Layer	1 D TC (W/m-K)
Reactive Bonded	40 (185 W/m-K) Measured	15 (5 W/m-K) From Model	45 (230 W/m-K) Measured	179
Pure Cu Prediction	25 (376 W/m-K)	19 (5 W/m-K)	57 (230 W/m-K)	225



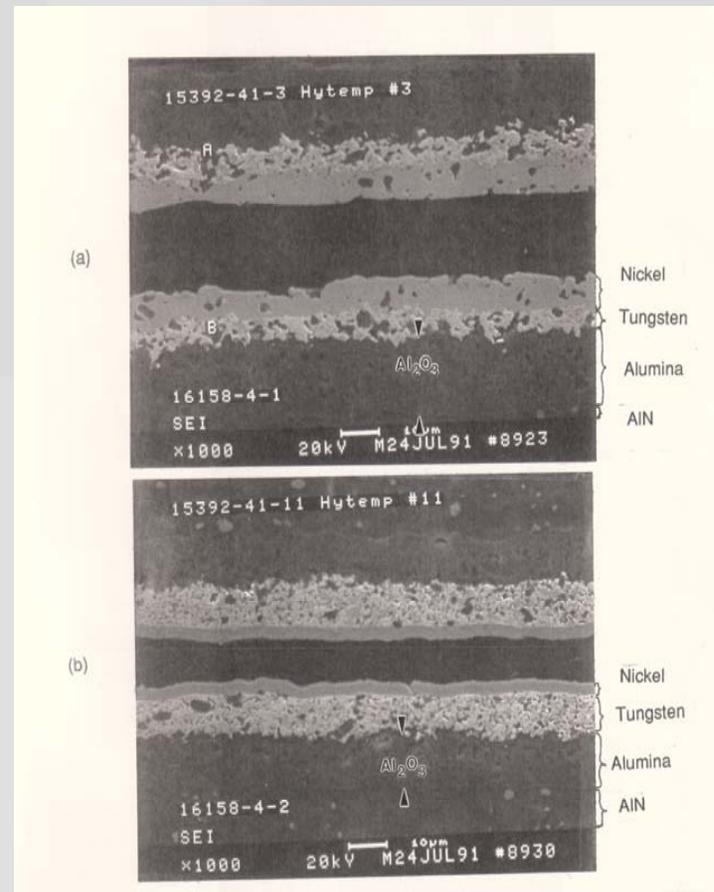
Thermal Impedance of Interfaces

- Tungsten Thick Film on Aluminum Nitride Ceramic
 - Post fire oxide bonding thick film
 - Co-fire
- Die Attach Materials
 - AuSi, AuSn
 - Silver Filled Epoxy



Tungsten Post Fire Thick Film on AlN

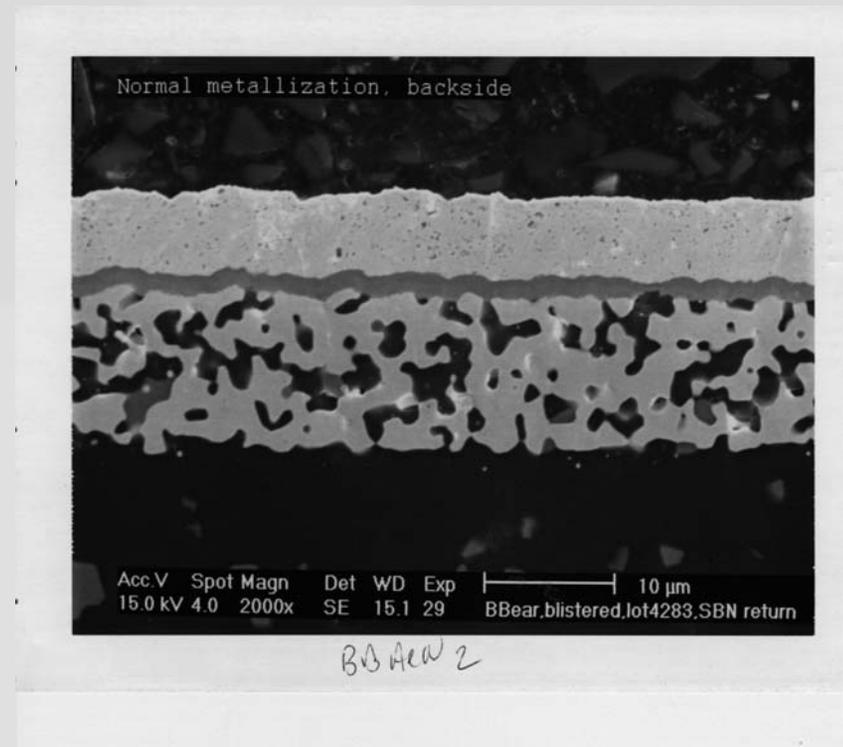
- Tungsten- Metal Oxide containing paste
- Oxide reaction with AlN to form bonding layer
- Porous oxide layer between the metallization and the high TC ceramic

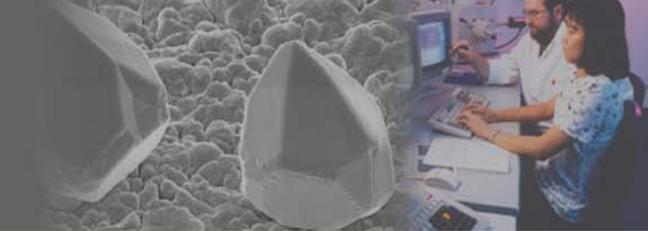




Tungsten Co-fire Thick Film on AlN

- Metal and Ceramic are co-sintered at 1825C
- Intimate contact between the metallization layer and the ceramic





Thermal Properties of Tungsten Bonded to AlN

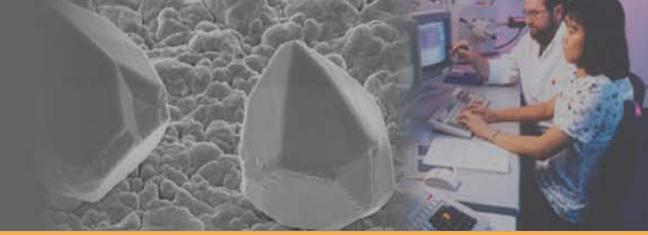
Percent of Total Thermal Resistance Contributed by Each Type of Layer

Sample	Two Metal Layers	Two Interface Layers	AlN Layer	1 D TC (W/m-K)
Thick Film Post-Fire	1 (180 W/m-K) 12 microns Measured	71 (3 W/m-K)	28 (190 W/m-K) 540 microns Measured	57
Co-Fired	3 (179 W/m-K) 18 microns Measured	0	97 (183 W/m-K) 1234 microns Measured	183

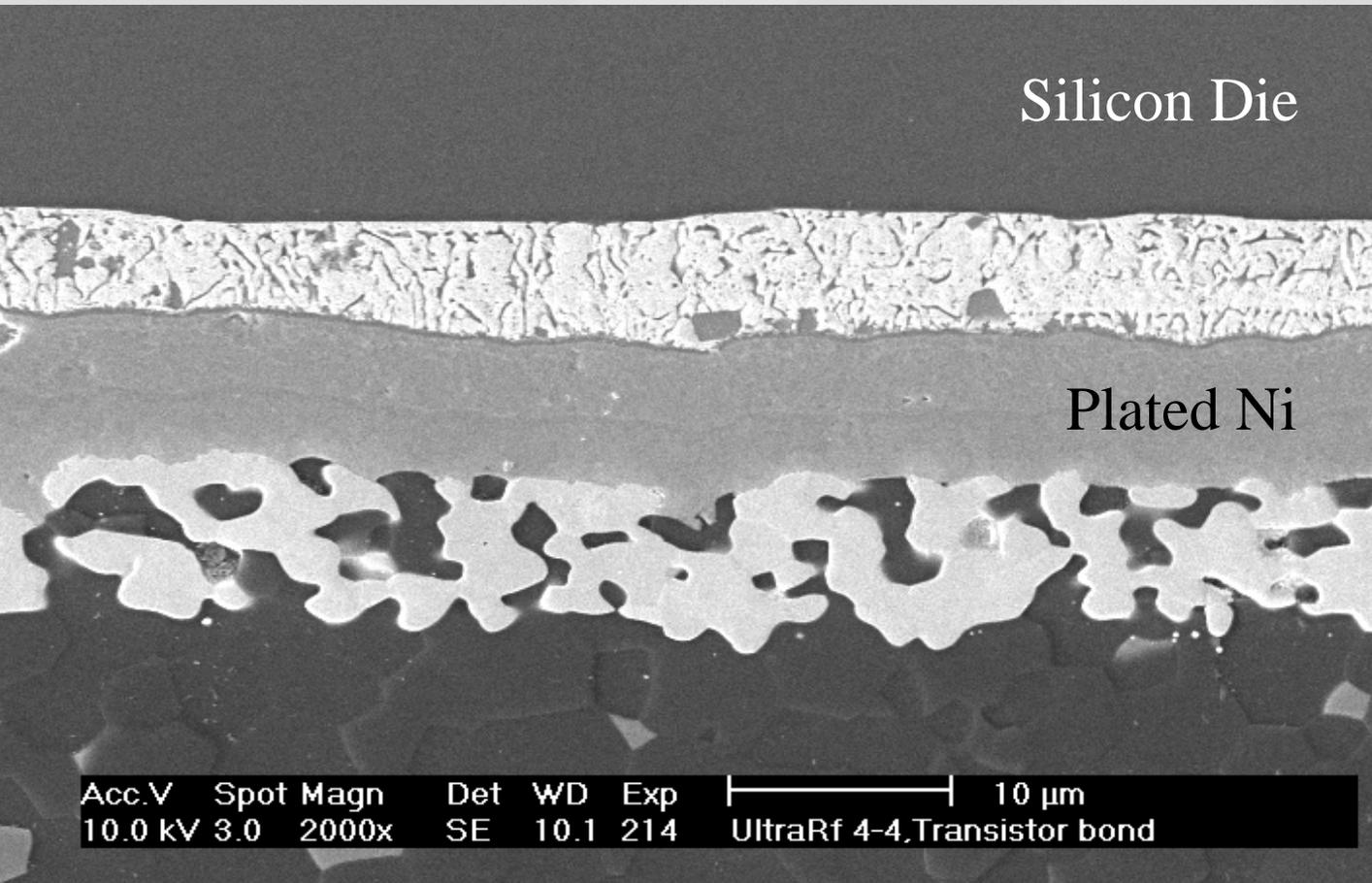


Application to other areas in packaging....

<u>Package Type or Application</u>	<u>Material Changes or Interface Issue</u>	<u>Impact</u>	<u>Solution</u>
GaAs MMIC, FET, semi-conductor laser	Ni diffusion into gold during AuSn die bond	Thermal conductivity decrease, wire bond issues	Control Au grain size to limit Ni diffusion, restrict die bonding time, Pt or Pd barrier layers
Silicon LDMOS and Bipolar for RF Power	Nickel silicide interface layer formation during AuSi die attach	Thermal barrier, die attach failure (brittle layer)	Plate with nickel cobalt to inhibit nickel silicide formation



Eutectic Die Attach: AuSi, AuSn



Silicon Die

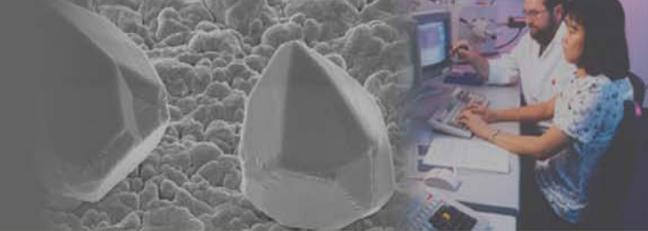
AuSi

Plated Ni

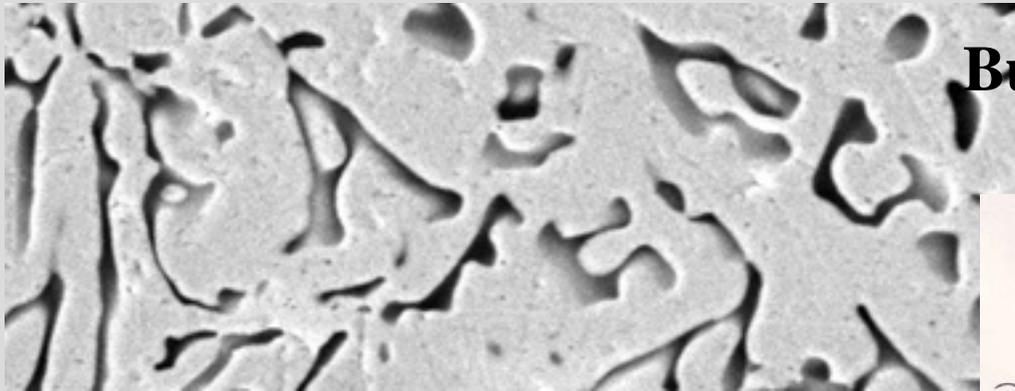
Tungsten metal

AlN Ceramic

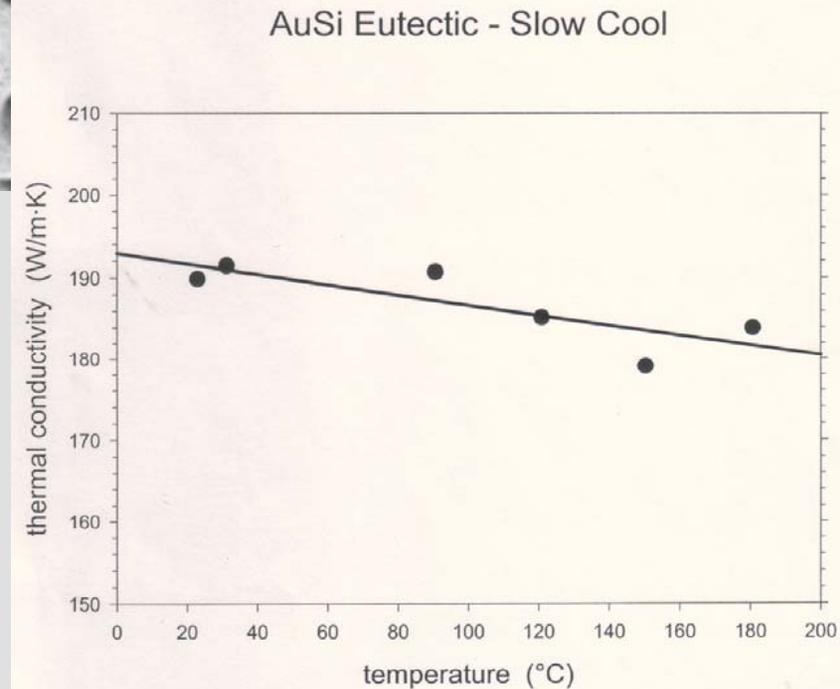
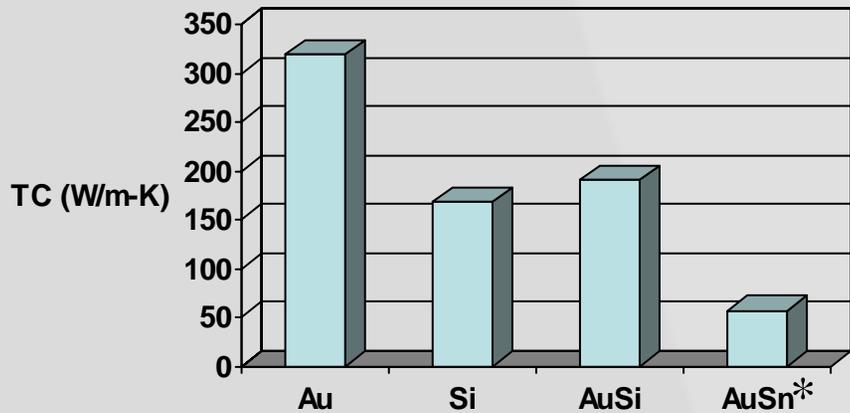
Acc.V Spot Magn Det WD Exp |-----| 10 μm
10.0 kV 3.0 2000x SE 10.1 214 UltraRf 4-4, Transistor bond



AuSi, AuSn Die Attach



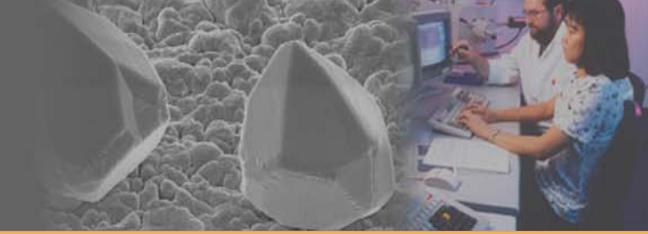
Bulk AuSi Sample ($\text{Au}_{82}\text{Si}_{18}$)



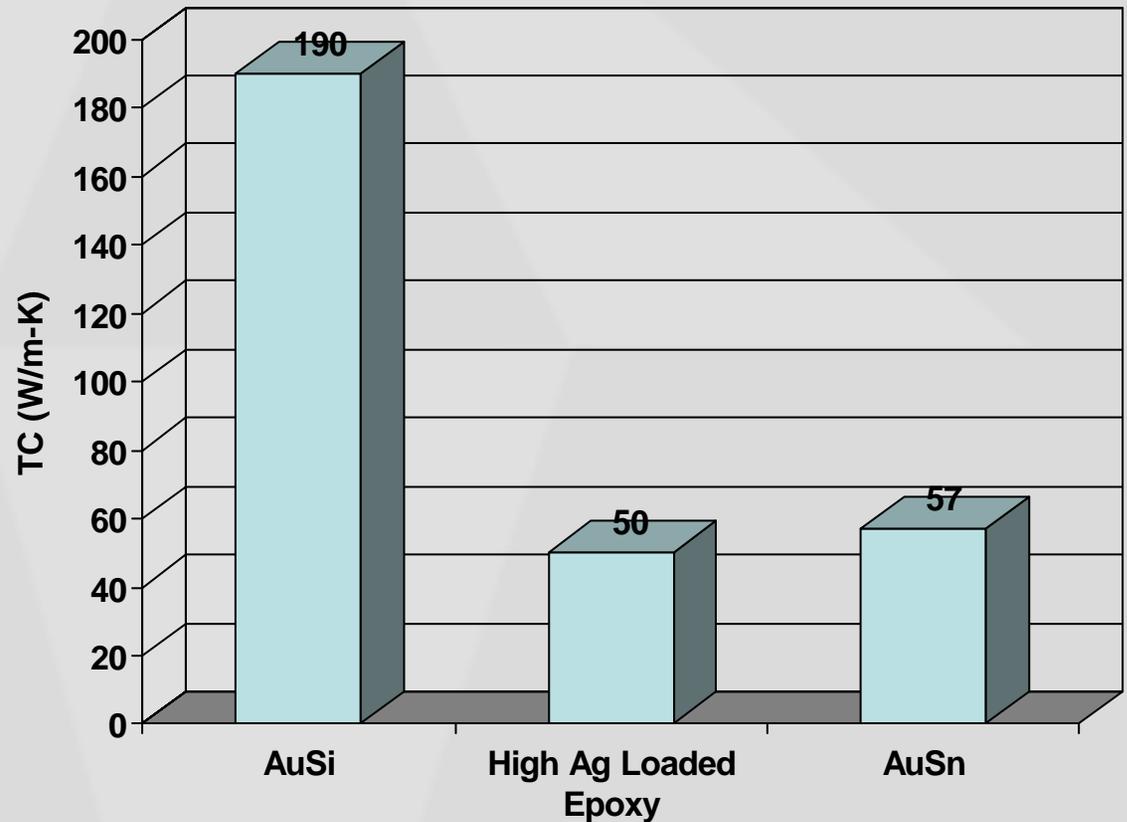


AuSi Thermal Conductivity- Controlling Factors

- Microstructure/Phase
 - Au₅Si (Fast cooled, metastable phase), TC= 15 W/m-K
 - Slow cooled Au/Si eutectic, TC = 190 W/m-K
- Silicon Dissolved in the Au Phase
 - 0.27 at. % Si in Au Solubility at Eutectic Temperature Johnson (1987)
 - In practice, function of cooling rate, Au grain structure

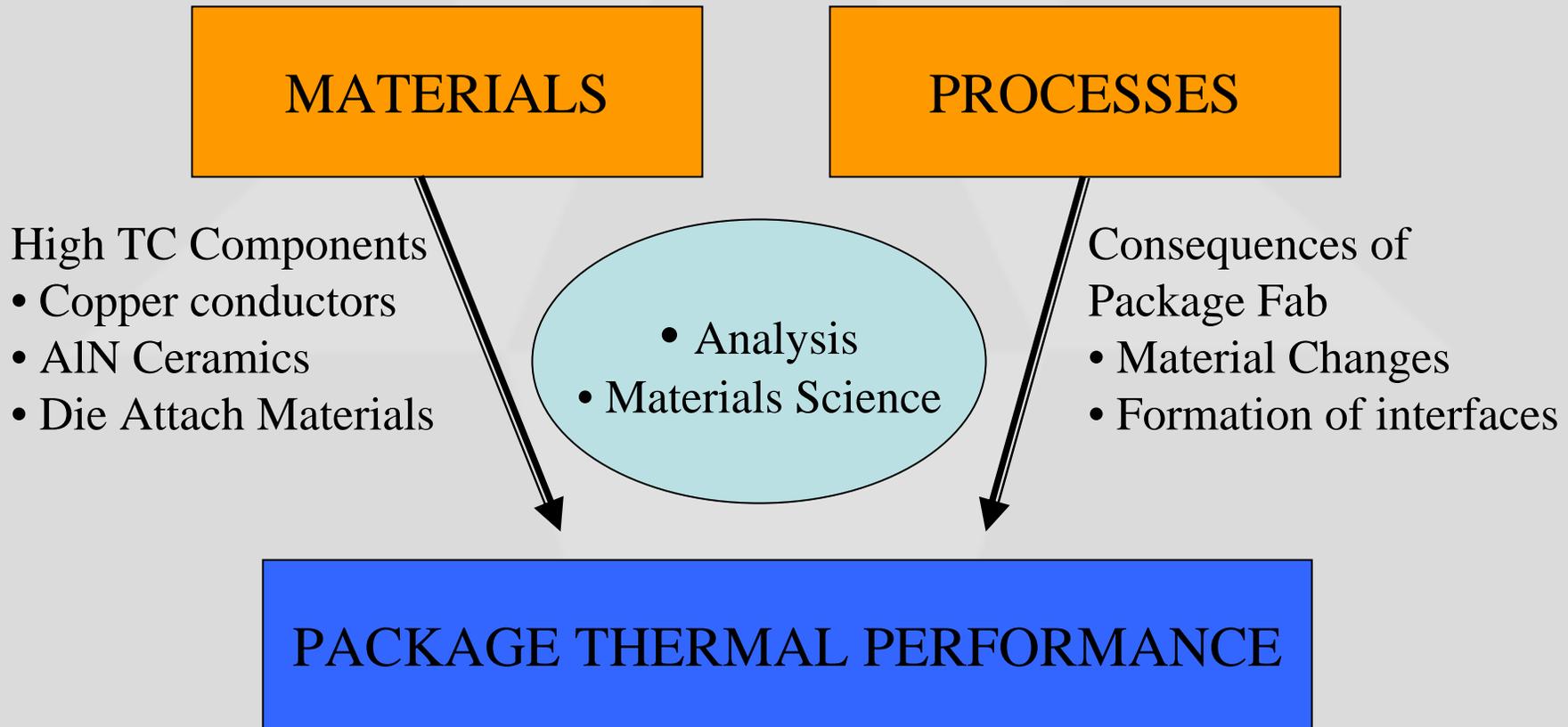


Thermal Conductivity Evaluation- Silver Filled Epoxy

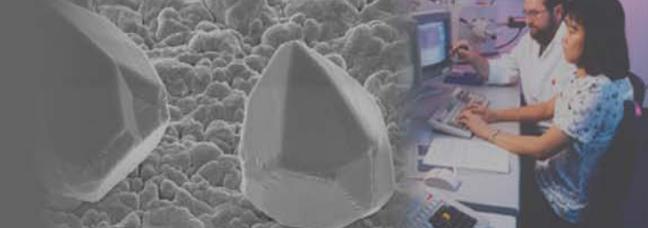




Both materials and fabrication processes strongly impact thermal performance.....



(Electrical Performance, Mechanical Properties, Reliability)



Packaging Technical Base

Electrical and Mechanical
Engineers

Materials Science

Thermal Conductivity Measurements
SEM/ Microstructural Analysis
Auger Spectroscopy
Phase analysis and equilibrium



Key Thermal Considerations for Packaging Applications- Summary

- Packages are constructed from heterogeneous “collection” of diverse materials
- Material alterations during fabrication and material interface formation have a profound effect on thermal performance
- **Material choice: Thermal Conductivity, Bonding Characteristics and Sensitivity to Fabrication Processes**